

WORKSHOP

ELECTRON BEAM LITHOGRAPHY AS A VEHICLE FOR NANOTECHNOLOGY APPLICATIONS

Main Auditorium "Themis Kanellopoulos"
NCSR "Demokritos"
Friday 15 February 2013

Agenda

09:30-09:45 Registration

09:45-10:00

Welcome

Dr. Nikos Glezos, Institute of Advanced Materials, Physicochemical Processes, Nanotechnology and Microsystems

10:00-10:30

Capabilities of the Nanotechnology and Microsystems Laboratory

Dr. Panagiotis Dimitrakis, Institute of Advanced Materials, Physicochemical Processes, Nanotechnology and Microsystems

10:30-11:15

E-Beam Lithography: Applications at Fraunhofer Institute for Telecommunication, Heinrich-Hertz-Institute

Dr. Ralf Steingrüber, Fraunhofer Institute for Telecommunication, Heinrich-Hertz-Institut, Berlin, Germany

11:15-11:30

Coffee Break

11:30-12:15

Application of e-beam lithography based patterning for the development of new nanoscale devices

Dr. Ivan Kostic, Institute of Informatics, Slovak Academy of Sciences, Bratislava, Slovakia

12:15-13:00

E-beam lithography: Enabling high resolution in 2D and 3D

Dr. Vitaliy Guzenko, Laboratory for Micro- and Nanotechnology, Paul Scherrer Institut, Villigen, Switzerland

13:00-13:30

The new EBPG5000plusES electron beam lithography system of NCSR "Demokritos"

Dr. Antonis Olziersky, Institute of Advanced Materials, Physicochemical Processes, Nanotechnology and Microsystems

13:30-14:00

Lunch break

14:00-15:00

Round Table Discussion

Exploitation of the E-beam facility by the Greek research community